

Laminar™ E9200

Dry Film Photoresist

Multi-functional Alkali Etch

Description

A universal photoresist system that works with nearly all PWB processes including ENIG and Immersion Silver.

Benefits

- Capable of 1:1 resolution
- Excellent performance in gold plating
- Fast clean processing
- Good donut and isolated resist adhesion
- New! 2.5 mil (63 μ) and 3.0 mil (75 μ) thickness



Laminar™ UD700

Dry Film Photoresist

For Laser Direct Imaging

Description

Specifically designed for Laser Direct Imaging (LDI) applications. This resist has demonstrated capability in a wide range of plating and etching applications.

Benefits

- Fast photo speed
- Capable of better than 1:1 resolution
- Superior adhesion
- Outstanding performance in alkaline or acid etching
- Excellent performance in plating applications



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